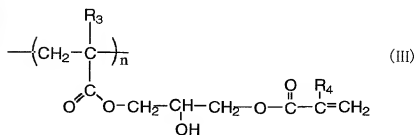
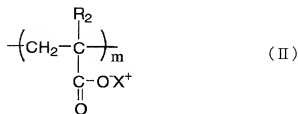
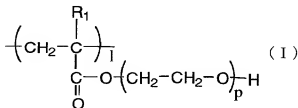
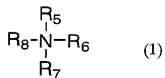


# ABSTRACT OF THE DISCLOSURE

The present invention provides a cross-linkable polymer compound which can be developed with an aqueous developer and exhibits excellent patterning properties; a photosensitive composition containing the same; and a pattern formation method employing the composition. The polymer compound containing monomer units represented by formulas (I) to (III):



wherein each of R<sub>1</sub> to R<sub>4</sub> is hydrogen and/or a methyl group; p represents an integer between 1 to 10 inclusive; X represents hydrogen, an alkali metal, or an ammonium represented by formula (1):



wherein each of  $R_5$  to  $R_8$  represents hydrogen, a C1-C3 alkyl group, or a C1-C3 alkanol group; and a plurality of Xs may be the same or different from one another, the compositional proportions of the monomer units falling within the following ranges: 2 mol%  $\leq l \leq 73$  mol%; 8 mol%  $\leq m \leq 83$  mol%; and 15 mol%  $\leq n \leq 80$  mol%.